



Docket No.: 0171-1045P
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hideo KANEKO et al.

Application No.: 10/724,734

Confirmation No.: 2079

Filed: December 2, 2003

Art Unit: 1756

For: METHODS OF MANUFACTURING
PHOTOMASK BLANK AND PHOTOMASK

Examiner: S. D. Rosasco

REPLY UNDER 37 C.F.R. § 1.111

MS RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

Concurrent with the filing of the present Request for Continued Examination and in further reply to the Office Action dated February 1, 2006, and the Advisory Action dated May 5, 2006, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This Reply includes: An Amended Set of Claims; and
Remarks.